WHAT IS CLAIMED IS:

- 1. A reaction product comprising at least
- a) acrylic acid or methacrylic acid or a mixture of acrylic or methacrylic acid and
- b) a (meth)acrylic ester of substituted or unsubstituted phenol, C₁-C₈-hydroxyalkylbenzene or C₁-C₈-hydroxyalkoxybenzene and methyl (meth)acrylate in the molar ratio of from 5:95 to 100:0,

5-90% of the acrylic or methacrylic acid units having reacted with a glycidylvinyl compound.

- 2. A reaction product according to claim 1, wherein component (a) is methacrylic acid.
- 3. A reaction product according to claim 1, wherein the (meth)acrylic ester of component (b) is benzyl methacrylate.
- 4. A reaction product according to claim 1, wherein the glycidylvinyl compound is glycidyl methacrylate.
- 5. A reaction product according to claim 1, wherein the molar ratio of component a) to component b) is from 85:15 to 15:85.
- 6. A reaction product according to claim 1, wherein the molecular weight of the reaction product is 10 000-120 000 g/mol.
- 7. A reaction product according to claim 1, wherein the molecular weight of the reaction product is 20 000-90 000 g/mol.



- 8. A reaction product according to claim 1, which has an acid number of 0.4-5.0 mol/kg, referred to the reaction product.
- 9. A photopolymerizable composition, substantially comprising
 - i) a reaction product according to claim 1,
 - ii) a monomeric or oligomeric acrylate having at least two ethylenically unsaturated, terminal groups,
 - iii) a polymerization initiator or initiator system which produces free radicals, cations or anions and can be activated by actinic radiation and,
 - iv) if desired, an organic or inorganic filler.
- 10. A photopolymerizable composition, substantially comprising
 - i) a reaction product according to claim 1,
 - ii) if desired, a monomeric or oligomeric acrylate having at least two ethylenically unsaturated, terminal groups,
 - iii) a polymerization initiator or initiator system which produces free radicals, cations or anions and can be activated by actinic radiation,
 - iv) if desired, an organic or inorganic filler,
 - v) a thermal polymerization inhibitor and
 - vi) a solvent or solvent system.
- 11. A photopolymerizable composition, substantially comprising
 - i) 15-70% by weight of the reaction product according to claim 1,
 - 0-30% by weight of monomeric or oligomeric acrylate having at least two ethylenically unsaturated, terminal groups,
 - iii) 0.1-15% by weight of a polymerization initiator or initiator system which produces free radicals, cations or anions and can be activated by actinic radiation,
 - iv) 0-60% by weight of an organic or inorganic filler,
 - v) 0.01-0.5% by weight of a thermal polymerization inhibitor and
 - vi) 20-80% by weight of a solvent or solvent system,

the percentages of the components being based on the total weight, with the proviso that the sum of the percentages by weight is 100.

- 12. A process for producing an etch resist image or solder resist image, comprising the process steps:
 - Application of a photopolymerizable composition according to claim 10 to a substrate;
 - II. removal of the solvent from the applied composition with formation of a film of the photopolymerizable composition on the substrate;
 - III. if desired, exposure of the coated substrate to actinic radiation;
 - IV. if desired, removal of the unexposed parts of the coating with the aid of an alkaline-aqueous or organic solvent with baring of the substrate; and
 - V. if desired, thermal curing and, if desired, UV curing of the coating remaining on the substrate.
- 13. A process according to claim 12, wherein the exposure (III) is effected with the aid of a photomask or directly by means of a laser.
- 14. A process for producing an etch resist image or solder resist image, comprising the process steps:
 - Application of the photopolymerizable composition according to claim 10 to a substrate by means of an inkjet method;
 - II. removal of the solvent from the applied composition with formation of a dried photopolymerizable composition on the substrate;
 - III. if desired, uniform exposure of the coated or structured substrate to actinic radiation; and
 - IV. if desired, thermal curing and, if desired, UV curing of the coating remaining on the substrate.

- 15. A photopolymerizable element comprising a substrate which carries a photopolymerizable layer, substantially comprising
 - A) 25-85% by weight of the reaction product according to claim 1,
 - B) 5-40% by weight of monomeric or oligomeric acrylate having at least two ethylenically unsaturated, terminal groups;
 - 1-25% by weight of an addition polymerization initiator or initiator system which produces free radicals, cations or anions and can be activated by actinic radiation;
 - D) 0-60% by weight of an organic or inorganic filler and
 - E) 0.025-1.0% by weight of a thermal polymerization inhibitor;

the percentages of the components being based on the total weight, with the proviso that the sum of the percentages by weight is 100, having a thickness of 0.1-400 μm .

16. A photopolymerizable element according to claim 15, wherein the thickness of the photopolymerizable layer is 3-50 µm.